

3600.0881-D5
February 12, 2001 (1:25PM)



U. Douglas
FEB 16 / 2001
Docket: AM-0881.D5

Amend
2/23/01
A

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: Robert D. Tolles et al.

Attorneys Docket: AM-0881.D5

Serial No.: 09/507,172

Art Unit No.: 3723

Filed: February 18, 2000

Examiner: unknown

For: "CHEMICAL MECHANICAL POLISHING SYSTEM HAVING MULTIPLE POLISHING STATIONS AND PROVIDING RELATIVE LINEAR POLISHING MOTION"

Commissioner of Patents and Trademarks
Washington, DC 20231

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TC 3760 MAIL ROOM

AMENDMENT UNDER 37 CFR §1.115

Sir:

In a Preliminary Amendment for consideration before initial examination, please amend the above application as follows:

In the claims:

Sub B1

A1

1. (Amended) A polishing apparatus, comprising:
a rotatable member rotatable about a first axis;
at least two polishing surfaces arranged at respective angular positions about said first axis;
at least one substrate head assembly supported on said rotatable member and capable of supporting [holding] thereon a substrate in contact with a selected one of said polishing surfaces and affording relative linear movement between said selected polishing surface and said substrate head assembly while said substrate supported on [held by] said substrate head is engaged with said selected polishing surface.

02/20/2001 AGOITOM 00000111 09507172

01 FC:103
02 FC:102

198.00 OP
240.00 OP